

INFORMATION DISCLOSURE CITATION <small>(Use several sheets if necessary)</small>			Docket Number (Optional) DE9-2000-006	Application Number 09/682,377			
			Applicant(s) Barber et al.				
			Filing Date 08/27/01	Group Art Unit UNKNOWN			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF TRADEMARK OFFICE	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JK	AA	5,290,361	03/01/94	Hayashida et al.	134		Jan. 23, 1992
	AB	5,373,629	12/20/94	Hupe et al.	205	852	Aug. 11, 1990
	AC	5,637,151	06/10/97	Schulz	134	2	Jun. 27, 1994
JK	AD	5,843,538	12/01/98	Ehram et al.	427	601	Nov. 14, 1997
JK	AE	5,849,170	12/15/98	Djokic et al.	205	163	Jun. 19, 1995
RECEIVED SEP 21 2001 TC 1700							
FOREIGN PATENT DOCUMENTS							
REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
JK	AF	METAL CONTAMINATION REMOVAL ON SILICON WAFERS USING DILUTE ACIDIC SOLUTIONS by O.J. Anttila and M.V. Tilli. J. Electrochem. Soc., Vol. 139, No. 6, June 1992. pp 1751 - 1756.					
EXAMINER <i>Hayashi</i>			DATE CONSIDERED 5/27/03				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.